

**Notice of References Cited**

Application/Control No.

10/534,199

Applicant(s)/Patent Under  
Reexamination  
ASPAR ET AL.

Examiner

Bradley K. Smith

Art Unit

2894

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**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
	D	US-			
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**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
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	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Bernard Terreault "Hydrogen blistering of silicon: Progress in fundamental understanding" Phys. Stat. Sol. (a) 204 No. 7, pp2129-2184 (2007)
	V	Duo et al. "Comparison between the different implantation orders in H+ and He+ coimplantation" J. Phys. D: Appl. Phys. 34 (2001) pp 477-482
	W	Weldon et al. "Mechanism of silicon exfoliation induced by hydrogen/helium co-implantation" Applied Physics Letters vol. 73 number 25, pp 3721-3723
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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